IN THE SPECIFICATION:

Please amend paragraph **[0021]** as follows:

[0021] Additionally, proper operation of a plasma reactor requires sound grounding techniques. Grounding plates 36 are illustrated and grounding may further take place through the use of a matchbox (not shown) or a counter electrode (not shown), the configuration and implementation of which is appreciated by those of ordinary skill in the art. Generally, a matchbox matches the impedance with the chamber and the generator. In short, the matchbox matches the impedance on both sides of the generator in order to minimize reflected power, which otherwise would result in an ineffective coupling of power into the plasma.

Please amend paragraph **[0030]** as follows:

[0030] Formation of a narrow gap via occurs as the plasma etching process proceeds over a continuum of time as defined by an etch rate and a resulting profile. The present embodiment varies the excitation of the power generators to advantageously formulate the plasma and the resulting electrical fields to select desirable etching characteristics over an entire etching process. In FIG. 4, various duty cycles are defined for the respective frequencies. In a first phase 80, generator signal 82 of upper power generator 12 (FIG. 1) is set to an active or defined level. Generator signal 84 of lower ~~low-frequency~~ high-frequency power generator ~~20~~ 18 (FIG. 1) is inactive. Additionally, generator signal 86 of lower low-frequency power generator 20 (FIG. 1) is also set to an active or defined level during first phase 80. The first phase configuration of power generators 12, 18 and 20 of the triple-frequency plasma reactor 10 (all of FIG. 1) similarly corresponds to the configuration as illustrated above with regard to FIG. 3B and correspondingly with the formation of an acceptable initial opening of narrow gap via 60 of FIG. 2B. Correspondingly, the narrow gap via 88 of FIG. 5 illustrates the formation of an initial opening during first phase 80.

Please amend paragraph **[0031]** as follows:

[0031] Returning to FIG. 4, a second phase 90 alters the excitation of power generators 12, 18 and 20 in an arrangement wherein generator signal 82 of upper power

generator 12 (FIG. 1) is inactive while generator signal 84 of lower high-frequency power generator 18 (FIG. 1) and generator signal 86 of lower low-frequency power generator 20 (FIG. 1) are set to active or defined levels. Such a configuration results, during second phase 90, of a more widened profile than would otherwise be attainable through the previous configuration as illustrated with reference to first phase 80. Such a resulting narrow gap via profile is illustrated with reference to FIG. 5. As a large aperture is desirable when mating with a target layer, such as target layer 92 of FIG. 5, a reconfiguration of the excitation of power generators 12, 18 and 20 is desirable. With reference to FIG. 4, a third phase 94 reconfigures the excitation in a manner consistent with the excitation of first phase 80, namely ~~frequencies~~ generator signals 82 and 86 of upper power generator 12 and lower low-frequency power generator 20, respectively, are set to active or defined levels while generator signal 84 of lower high-frequency power generator 18 (FIG. 1) is inactive. Such a configuration of the excitation of the corresponding power generators enables the formation of a more desirably larger aperture when coupling with target layer 92.